



PTO-1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. 213.003-D1-US	SERIAL NUMBER 10/756,718
	APPLICANT(S) Ye et al.	
	FILING DATE January 13, 2004	GROUP ART UNIT 2825 2857

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EXAMINER	Richard Foyard	DATE CONSIDERED	2/24/05
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EXAMINER	<i>Adrian D. Kuykendall</i>	DATE CONSIDERED	2/24/05
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